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Substitute for form 1449/PTO INFORMATION DISCLOSURE STATEMENT BY APPLICANT <i>(Use as many sheets as necessary)</i>				Complete if Known	
				Application Number	10/596,626-Conf. #8534
				Filing Date	June 19, 2006
				First Named Inventor	Karl-Heinz Schuster
				Art Unit	N/A
				Examiner Name	Not Yet Assigned
Sheet	1	of	1	Attorney Docket Number	01641/0204258-US0

U.S. PATENT DOCUMENTS					
Examiner Initials*	Cite No. ¹	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number-Kind Code ² (if known)			
	AA*	US-6,717,722	04-06-2004	Shafer et al.	
	AB*	US-2005/0190455-A1	09-01-2005	Rostalski et al.	
	AC*	US-2005/0225737-A1	10-13-2005	Weissenrieder et al.	
	AD*	US-2006/0012885-A1	01-19-2006	Beder et al.	
	AE*	US-6,995,930	02-07-2006	Shafer et al.	
	AF*	US-2006/0221456-A1	10-05-2006	Shafer et al.	
	AG*	US-2003/0174408-A1	05-10-2005	Rostalski et al.	
	AH*	US-2002/0102497-A1	10-07-2003	Sparrow	
	AI*	US-4,861,148	08-29-1989	Sato et al.	
	AJ*	US-6,025,115	02-15-2000	Komatsu et al.	

FOREIGN PATENT DOCUMENTS						
Examiner Initials*	Cite No. ¹	Foreign Patent Document	Publication Date	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T ⁶
		Country Code ³ -Number ⁴ -Kind Code ⁵ (if known)	MM-DD-YYYY			
	BA	WO-2004/019128	03-04-2004	Nikon Corporation		✓
	BB	WO-2005/081067	09-01-2005	CARL ZEISS SMT AG		✓
	BC	WO-2005/106589	11-10-2005	CARL ZEISS SMT AG		✓
	BD	EP-0 475 020-A	03-18-1992	International Business Machines Corporation		✓
	BE	WO-2005/059654	06-30-2005	Carl Zeiss SMT AG		✓

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NON PATENT LITERATURE DOCUMENTS			
Examiner Initials	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ⁶
	CA	Smith, B. W. et al., "Water Immersion Optical Lithography for the 45nm Node", <i>Optical Microlithography XVI, Proceedings of SPIE</i> (2003) Vol. 5040; 679-689	
	CB	Smith, B.W. et al., "Approaching the numerical aperture of water-immersion lithography at 193nm", <i>Optical Microlithography XVII, Proceedings of SPIE</i> , Vol. 5377; 273-284	
	CC	Burnett, J.H. et al., "High Index Materials for 193 nm and 157 nm Immersion Lithography", International Symposium on Immersion & 157 nm Lithography, Vancouver, 8/2/2004	

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